

PROCESSING APPARATUS

ABSTRACT

A processing apparatus includes a processing chamber cover having a first transverse member extending from between a first side plate and a first delivery port defined in the first side plate outwardly of a first processing chamber. In the processing apparatus, the width of a gap between the first transverse member and a pedestal positioned in the first delivery port when a workpiece is processed in the first processing chamber, i.e., the length of the gap along the direction toward the outside of the processing chamber, is large. When processing water that is scattered passes through the gap, it is highly probable for the processing water to contact the pedestal or the first transverse member and stay in the gap. As a result, the processing water is effectively prevented from being scattered out of the first processing chamber by a simple structure, compared with water supply means for forming a water film in the gap.

[FIG. 3]